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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/044,178	01/10/2002	Todd Edgar	MIO 0011 N2	3193	
7590 07/21/2005			EXAMINER		
Killworth, Gottman, Hagan & Schaeff, L.L.P.			LE, THAO X		
Suite 500		ART UNIT	PAPER NUMBER		
One Dayton Centre			ARTUNIT	PAPER NUMBER	
Dayton, OH 45402-2023			2814		
			DATE MAILED: 07/21/2005	DATE MAILED: 07/21/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/044,178	EDGAR, TODD			
Office Action Summary	Examiner	Art Unit			
	Thao X. Le	2814			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be timed within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nety filed s will be considered timely. the mailing date of this communication. O (35 U.S.C. § 133).			
Status	·				
1) Responsive to communication(s) filed on 10 July 2a) This action is FINAL. 2b) This 3) Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro				
Disposition of Claims					
4) ☐ Claim(s) 1-5 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-5 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or					
Application Papers					
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acce Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	epted or b) objected to by the Eddrawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>					
Attachment(s).  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:				

#### **DETAILED ACTION**

### Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1-5 are rejected under 35 U.S.C. 103(a) as being unpatentable over US 5028990 to Kotaki et al. in view of US 5327375 to Harari

Regarding claim 1, Kotaki discloses a storage container structure in fig. 10 comprising: a substrate 1, column 3 line 21, including a semiconductor structure; an insulating overlayer 6/8 disposed over and in contact with said substrate, insulating overlayer 6, column 4 line 25, including a container region 9 (groove), fig. 4b/9, disposed therein, said container region 9 defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by said container side walls and said container bottom wall; a patterning stop region 5b, column 3 line 23, fig. 10, disposed over said substrate 1 such that all of said container bottom wall is defined by an upper surface of said patterning stop region 5b, fig. 9; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region (where 16 is located) defined by said charge storage lamina, wherein said contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein said contact region side walls and

said contact region bottom wall are defined by a first surface of said charge storage lamina, fig. 10, and an electrical contact 16, column 4 line 68, in said contact region, wherein respective portions of said electrical contact 16 and said charge storage lamina 12/13/14 occupy collectively at least a portion of said container region.

But, Kotaki does not disclose a storage container structure such that a substantial entirely of the width of said container region is defined by an upper surface of said patterning stop region.

However, Harari disclose a storage container structure comprises a lamina (P2/C/P3) such that a substantial entirely or partially of the width of said container region is defined by an upper surface of said patterning stop region 1502 or 1602 as shown in fig. 8A-B. At the time the invention was made; it would have been obvious to one of ordinary skill in the art to use storage container structure configuration teaching of Harari with Kotaki's storage container, because such configuration would have created an art recognized suitability for an intended purpose, MPEP 2144.07. Furthermore, such storage container would have enhanced charge storage capacity by increasing the surface area between the two electrodes as taught by Harari.

Regarding claim 2, Kotaki discloses a storage container structure in fig. 10 comprising: a substrate 1 including a semiconductor structure; a patterning stop region 5B with a lower surface substantially coplanar with the top of said substrate1, fig. 10; an insulating overlayer 6 over said substrate, said insulating overlayer 6 comprising: a lower overlayer surface (bottom surface of 6) positioned over said substrate 1, wherein

said lower overlayer surface is in contact with said top of said substrate 1, fig. 10, an upper overlayer surface (top surface of 6) and an intermediate overlayer 8 portion defined between said lower overlayer surface 6 and upper overlayer surface; a container region 9 within said insulating overlayer 6, container region 9 defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall, wherein all of container bottom wall is defined by an upper surface of said patterning stop region 5B, a charge storage lamina 12/13/14 over an interior surface of said container region 9: a contact region (where 16 is located) defined by said charge storage lamina, wherein said contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein said contact region side walls and said contact region bottom wall are defined by a first surface of said charge storage lamina 12/13/14, and an electrical contact 16 in said contact region, wherein respective portions of said electrical contact and said charge storage lamina occupy collectively at least a portion of said container region, fig. 10.

But, Kotaki does not disclose a storage container structure such that a substantial entirely of the width of said container region is defined by an upper surface of said patterning stop region.

However, Harari disclose a storage container structure comprises a lamina (P2/C/P3) such that a substantial entirely or partially of the width of said container region is defined by an upper surface of said patterning stop region 1502 or 1602 as shown in fig. 8A-B. At the time the invention was made; it would

have been obvious to one of ordinary skill in the art to use storage container structure configuration teaching of Harari with Kotaki's storage container, because such configuration would have created an art recognized suitability for an intended purpose, MPEP 2144.07. Furthermore, such storage container would have enhanced charge storage capacity by increasing the surface area between the two electrodes as taught by Harari.

Regarding claim 3, Kotaki discloses a storage container structure comprising: a substrate 1 including a semiconductor structure, said substrate including a generally planar upper surface; an insulating overlayer 6 disposed over and in contact with said generally planar upper surface of said substrate 1, said insulating overlayer including a container region 9 disposed therein, said container region defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall; a patterning stop region 5B including: a lower surface substantially coplanar with generally planar upper surface of substrate 1; and an upper surface configured such that the lowermost extension of container bottom wall does not project substantially below upper surface of said patterning stop region 5B; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region (where 16 is located) defined by said charge storage lamina, wherein contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein contact region side walls and contact region bottom wall are defined by a first surface of charge storage lamina 12/13/14; and an electrical contact 16 in contact region, wherein

respective portions of electrical contact and charge storage lamina occupy collectively at least a portion of container region 9, fig. 10.

But, Kotaki does not disclose a storage container structure such that a substantial entirely of the width of said container region is defined by an upper surface of said patterning stop region.

However, Harari disclose a storage container structure comprises a lamina (P2/C/P3) such that a substantial entirely or partially of the width of said container region is defined by an upper surface of said patterning stop region 1502 or 1602 as shown in fig. 8A-B. At the time the invention was made; it would have been obvious to one of ordinary skill in the art to use storage container structure configuration teaching of Harari with Kotaki's storage container, because such configuration would have created an art recognized suitability for an intended purpose, MPEP 2144.07. Furthermore, such storage container would have enhanced charge storage capacity by increasing the surface area between the two electrodes as taught by Harari.

Regarding claim 4, Kotaki discloses a storage container structure comprising: a substrate 1 including a semiconductor structure, substrate 1 including a generally planar upper surface, an insulating overlayer 6 disposed over and in contact with said generally planar upper surface of substrate, insulating overlayer 6 including a container region 9 disposed therein, container region defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall; a patterning stop region 5B

including: a lower surface substantially coplanar with said generally planar upper surface of said substrate, fig. 10, and an upper surface substantially coplanar with said container bottom wall; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region defined by charge storage lamina, wherein contact region (where 16 is located) defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein contact region side walls and contact region bottom wall are defined by a first surface of charge storage lamina; and an electrical contact 16 in contact region, wherein respective portions of electrical contact 16 and charge storage lamina 12/13/14 occupy collectively at least a portion of container region, fig. 10.

But, Kotaki does not disclose a storage container structure such that a substantial entirely of the width of said container region is defined by an upper surface of said patterning stop region.

However, Harari disclose a storage container structure comprises a lamina (P2/C/P3) such that a substantial entirely or partially of the width of said container region is defined by an upper surface of said patterning stop region 1502 or 1602 as shown in fig. 8A-B. At the time the invention was made; it would have been obvious to one of ordinary skill in the art to use storage container structure configuration teaching of Harari with Kotaki's storage container, because such configuration would have created an art recognized suitability for an intended purpose, MPEP 2144.07. Furthermore, such storage container

would have enhanced charge storage capacity by increasing the surface area between the two electrodes as taught by Harari.

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Regarding claim 5, Kotaki discloses a storage container structure according to claim 4, wherein said upper surface of patterning stop region 5B is configured such that all of container bottom wall is defined by said upper surface of said patterning stop region 5B, fig. 10.

## Response to Arguments

3. Applicant's arguments with respect to claims 1-5 on 10 June 2005 have been considered but are most in view of the new ground(s) of rejection.

#### Conclusion

4. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao X. Le whose telephone number is (571) 272-1708. The examiner can normally be reached on M-F from 8:00 AM - 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M. Fahmy can be reached on (571) 272 -1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov\_Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao X. Le Patent Examiner 11 July 2005. LONG PHAM DRIMARY EXAMINER